

Electronic Patent Application Fee Transmittal

Application Number:	10587194			
Filing Date:	24-Jul-2006			
Title of Invention:	Protected pattern mask for reflection lithography in the extreme uv or soft x-ray range			
First Named Inventor/Applicant Name:	Jean-Louis Stehle			
Filer:	Peter C. Hsueh/C Healion			
Attorney Docket Number:	58059/N75			

Filed as Large Entity

U.S. National Stage under 35 USC 371 Filing Fees

Description	Fee Code	Quantity	Amount	Sub-Total in USD(\$)
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Basic Filing:

Pages:

Claims:

Miscellaneous-Filing:

Petition:

Patent-Appeals-and-Interference:

Post-Allowance-and-Post-Issuance:

Extension-of-Time:

Extension - 3 months with \$0 paid	1253	1	1110	1110
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Description	Fee Code	Quantity	Amount	Sub-Total in USD(\$)
Miscellaneous:				
Total in USD (\$)				1110